

# ***Laser Micromachining of Bulk Substrates and Thin Films***

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# Outline

- Oxford Lasers
- Importance of various parameters
- Examples of Machining bulks substrates with ns, ps, fs lasers
- Examples of Machining thin films



- Didcot, Oxon (UK), Boston (USA), Paris (France)
- Founded in 1977 (Excimer and Copper Laser Manufacturer)

Oxford University spinout (inventor gas preionisation technique)

- Two divisions: (a) Laser micromachining  
(b) High-speed imaging
- Markets: microelectronics, solar, healthcare, automotive, biomedical, telecoms etc etc

## We offer:

- Turn-key Laser Micromaching Systems
- Sub-contract Laser Micromachining
- Proof-of-Concept Trials, Contract R and D



# Importance of laser wavelength

The laser wavelength and material optical properties determine **light absorption** (i.e. the extent to which the material takes up the deposited energy)

Incident laser light on surface = [reflected] + [absorbed] + [transmitted]

Only **[absorbed]** light in the material is useful for *Laser Micromachining* and the optical penetration (absorption) depth defines the process resolution

## Beer-Lambert law

(assuming linear absorption)

$$I_1 = I_0 \exp [-\alpha L]$$

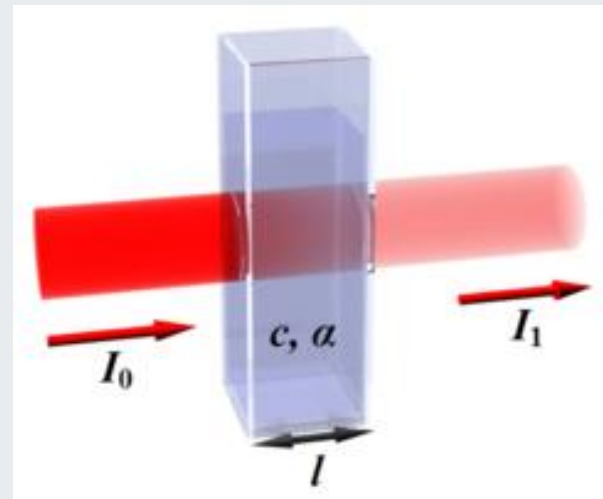
$I_0$  (W/cm<sup>2</sup>) ; incident intensity after reflection

$I_1$  (W/cm<sup>2</sup>) ; transmitted intensity

$\alpha$  (cm<sup>-1</sup>) ; material absorption coefficient

$L$  (cm) ; material thickness

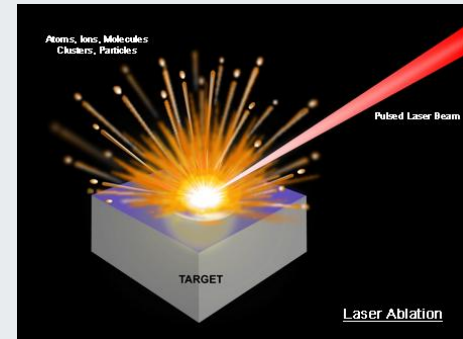
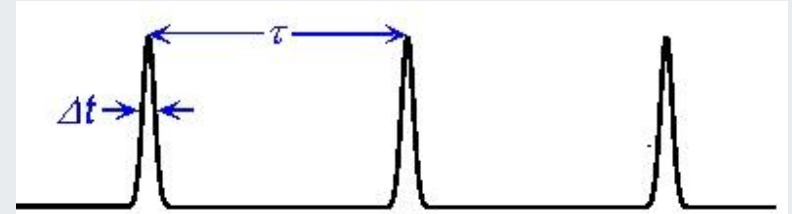
$1/\alpha$  : optical penetration depth (typically in  $\mu\text{m}$ )



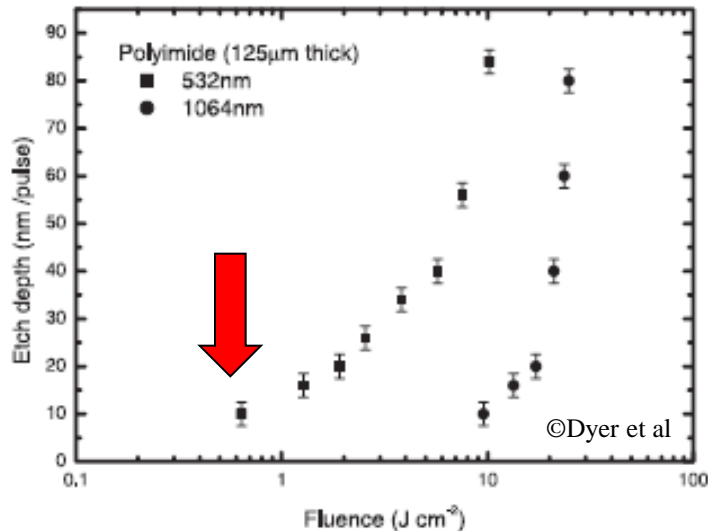
# Importance of laser output and pulse frequency

The laser output and pulse frequency define the **maximum pulse energy** available in each laser pulse and the **maximum rate** that energy can be delivered to the sample surface.

*Note: Too high pulse energy or pulse frequency can result in target cumulative heating and thermal damage - if thermalisation is faster than heat dissipation in the material.*

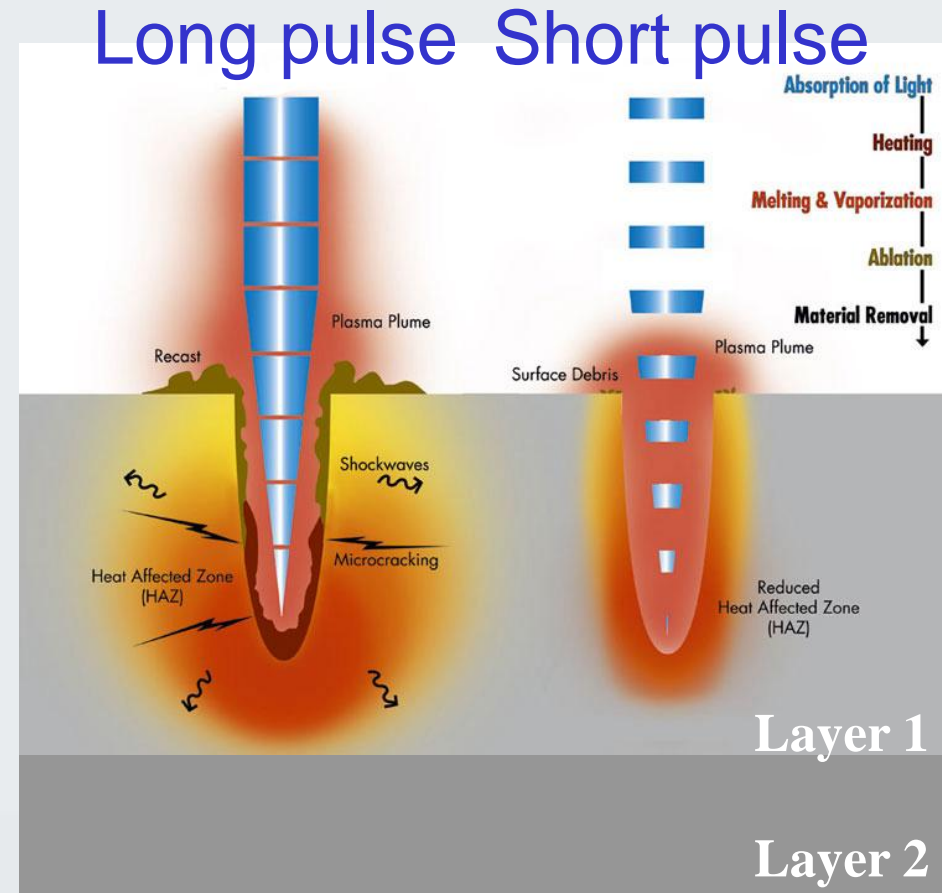


If enough energy is delivered on the surface to exceed the **ablation threshold**, material removal begins called **laser ablation** and soon a crater is formed



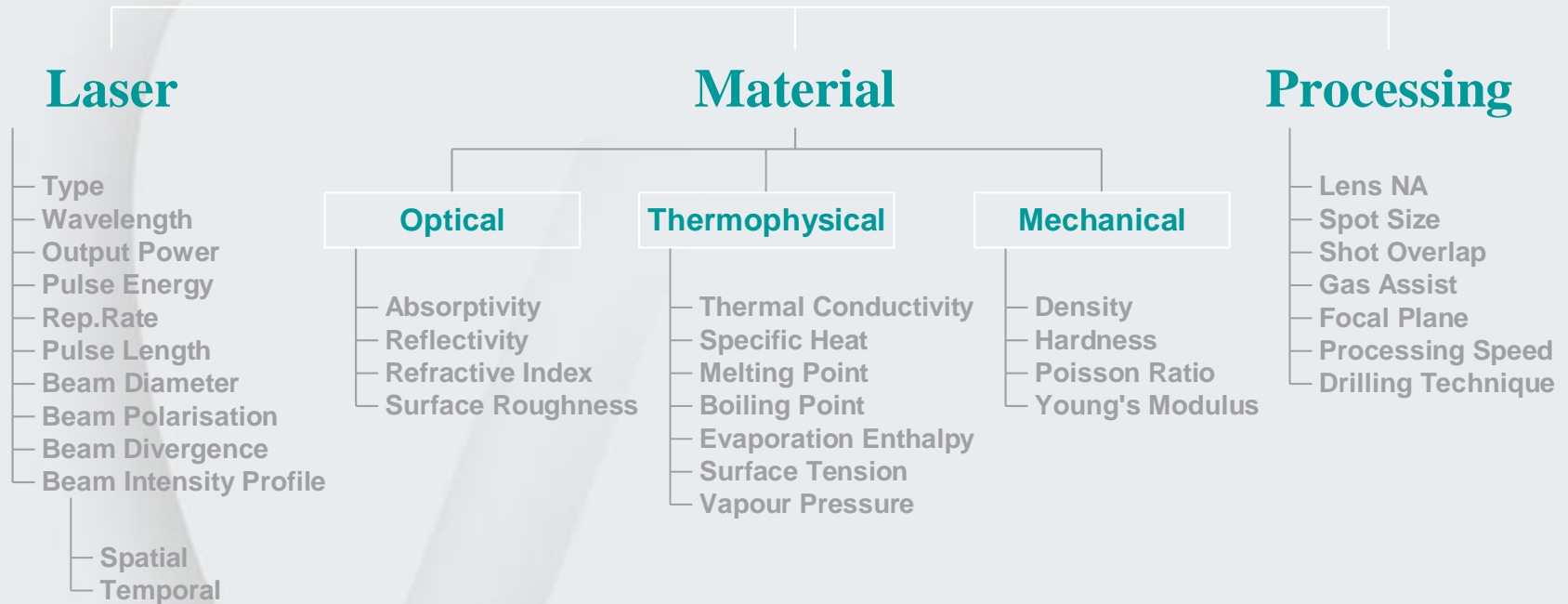
# Importance of laser pulse duration

- Longer pulses (>10ns) associated
  - Thermal ablation processes
  - Prolonged laser+plasma heating
  - Beam attenuation losses
  - Melting and recast debris (evident)
  - Heat affected zone, HAZ (hidden)
  - High removal rates
  
- Shorter pulses (<0.1ns)
  - “Cold” ablation processes
  - Shorter plasma lifetime
  - Rapid energy deposition (less debris)
  - Deterministic ablation thresholds
  - Restricted HAZ
  - Low removal rate



The laser pulse duration determines the “**heat spreading**” in the material, crucial here is a lack of heat spreading for thin-film ablation.

# Optimisation parameters



**! IMPORTANT NOTE:**

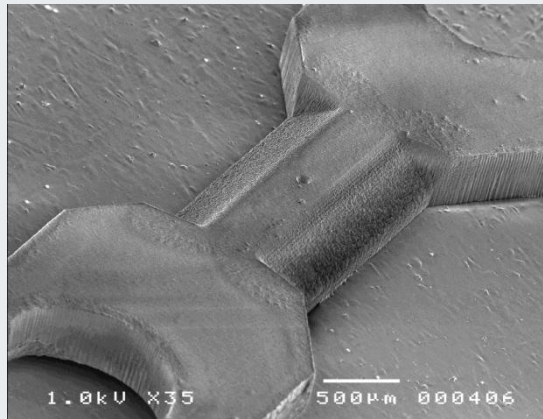
**Process is key !!!**



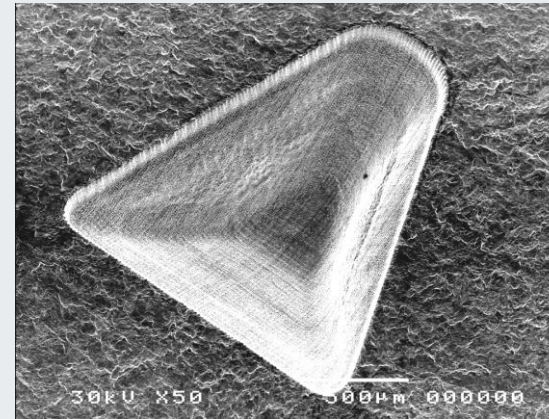
# Nanosecond Pulse Ablation : Micro-Milling

Examples of optimised processes with nanosecond laser sources

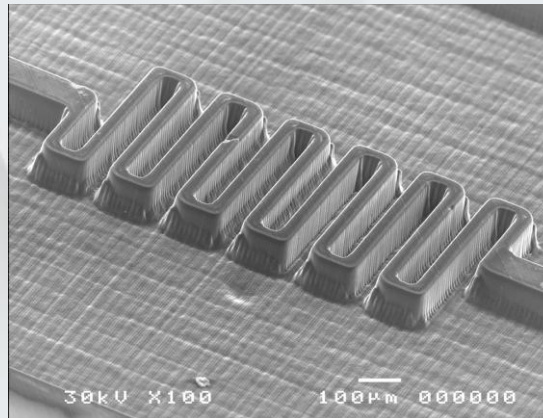
Alumina



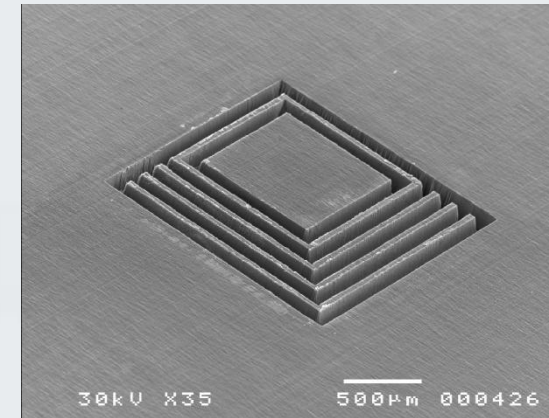
Tungsten



Diamond



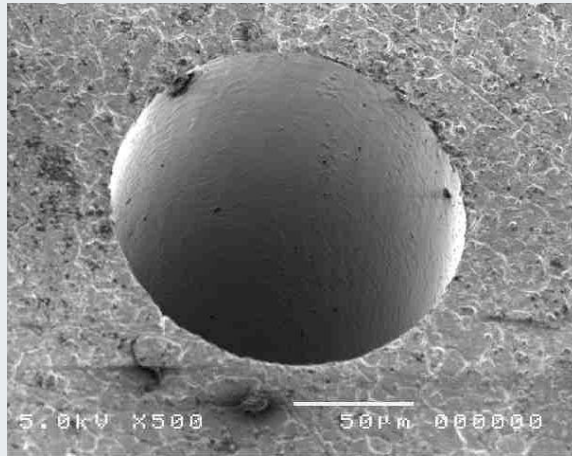
Polyimide



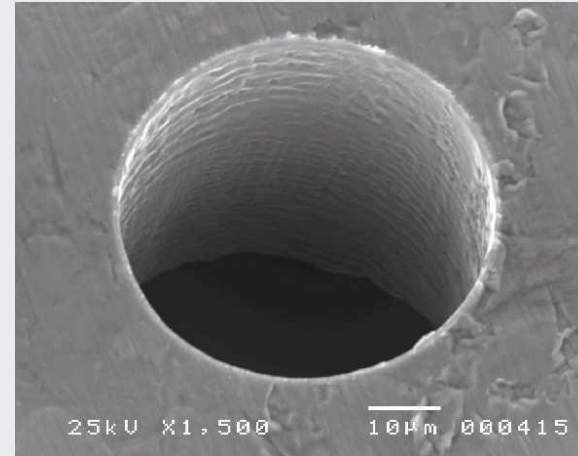


# Micro-Drilling

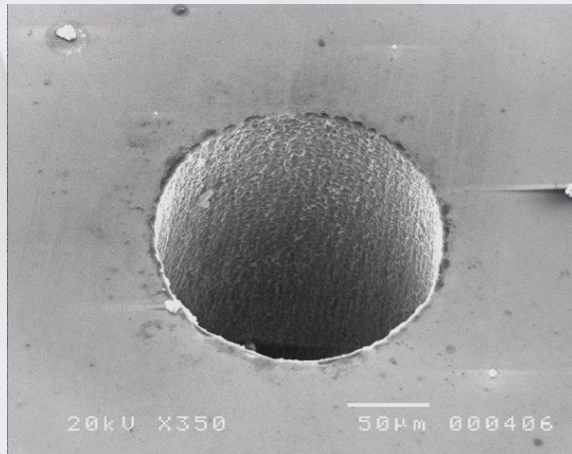
150  $\mu\text{m}$  dia  
thro' 1mm  
steel



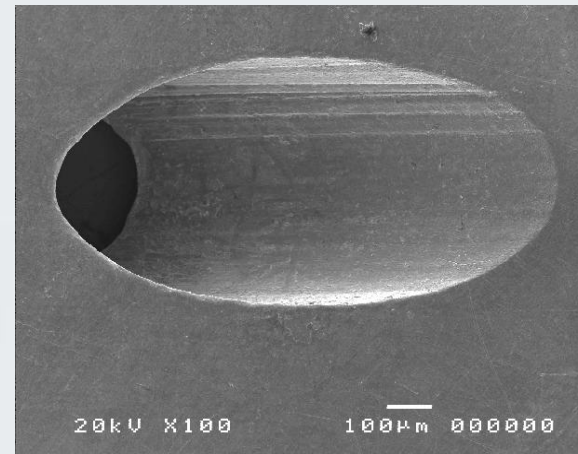
50  $\mu\text{m}$  dia  
thro' 0.1mm  
steel



150  $\mu\text{m}$  dia  
thro' 0.5mm  
silicon

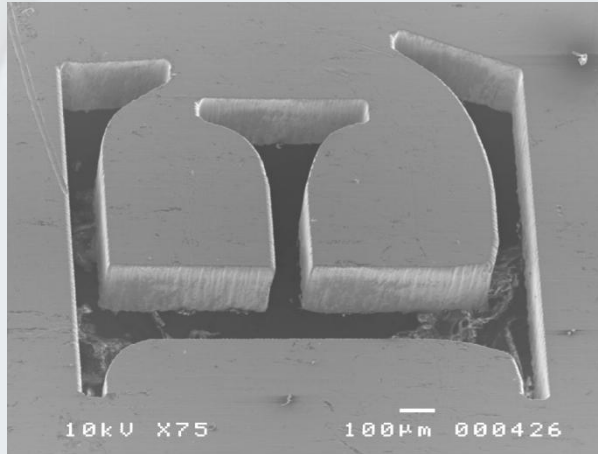


30 degree  
hole in steel

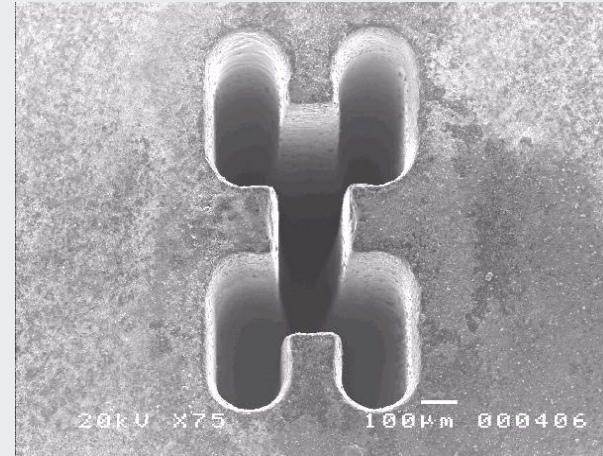


# Micro-Cutting

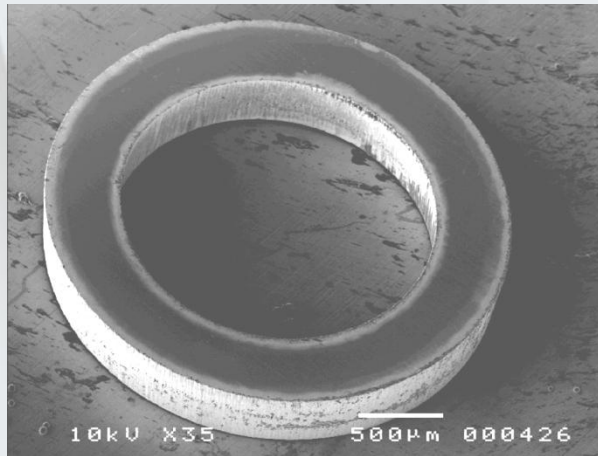
Steel



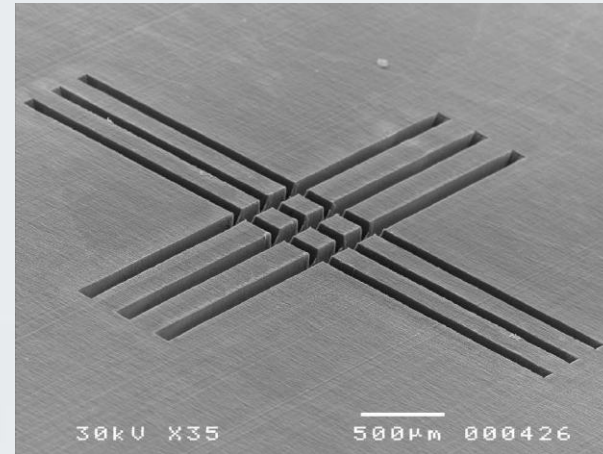
Diamond



Silicon



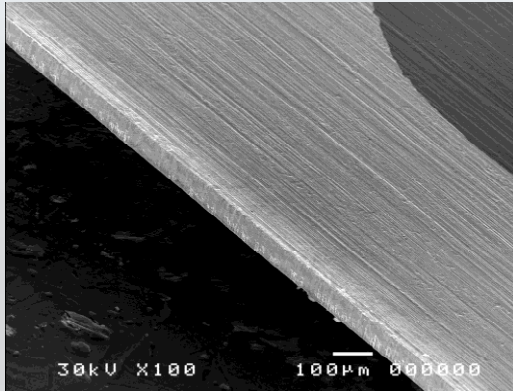
Polyimide



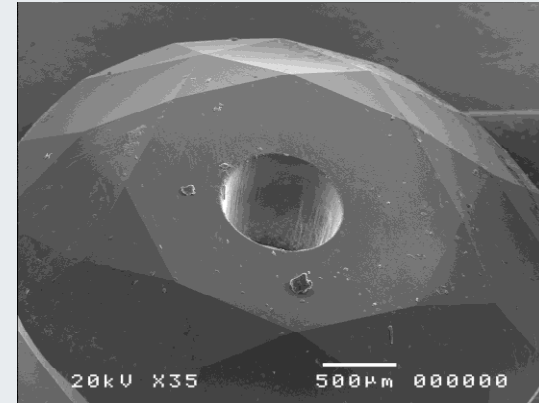
Expert Process Technology

*... 20 years experience in laser micromachining*

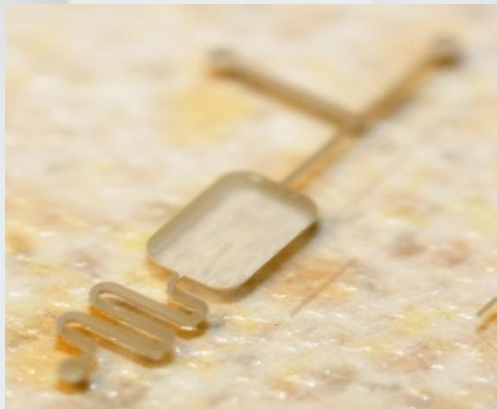
# Examples of ps laser machined features



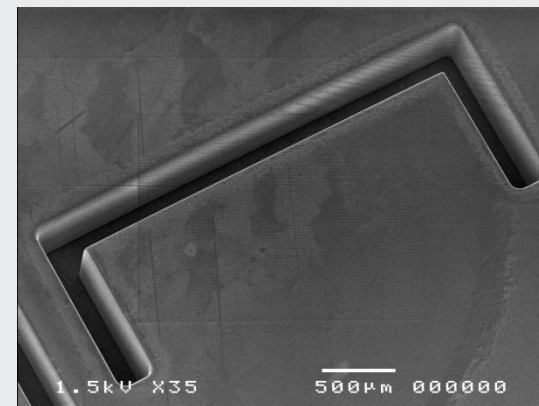
Nickel



Diamond



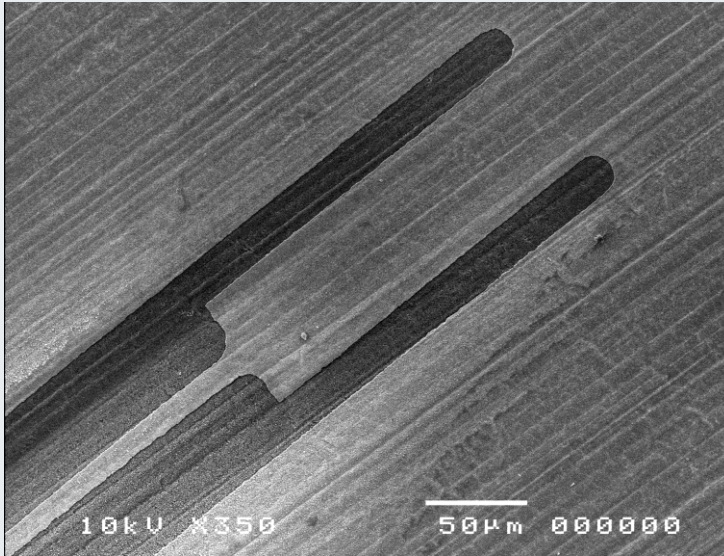
Borosilicate



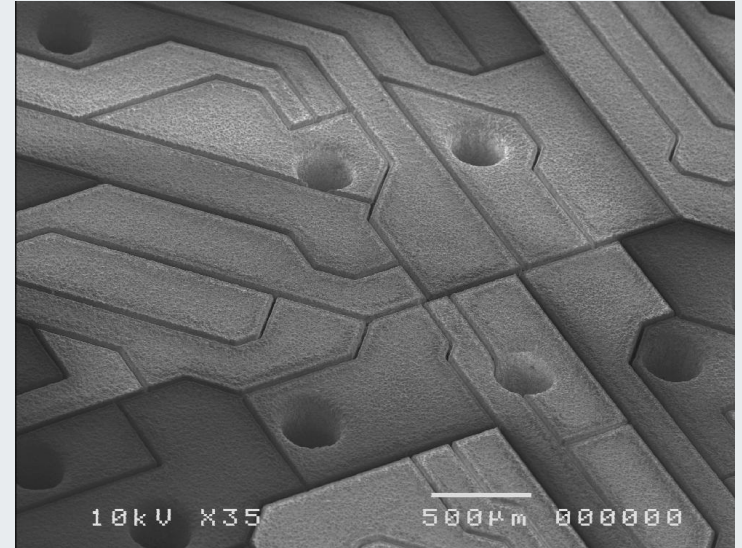
Sapphire



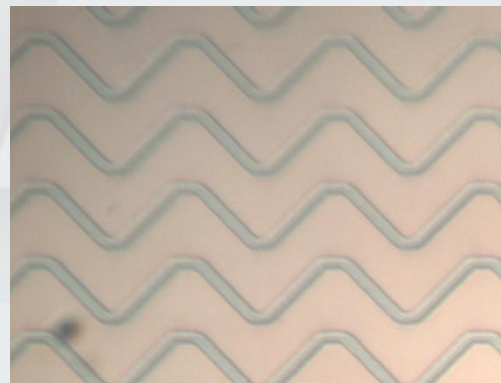
# Thin Films Laser Ablation : Ps/Fs Lasers



**Patterning** – Gold on Ti on Polymer  
20 -45 micron wide tracks



**Patterning** – 17 microns Cu on FR4



**Patterning** – ITO on Glass  
10 micron wide tracks on 70 micron pitch

# Transparent Materials

## Organic LED Production (thin film removal)

### OLEDs advantages over LCDs -

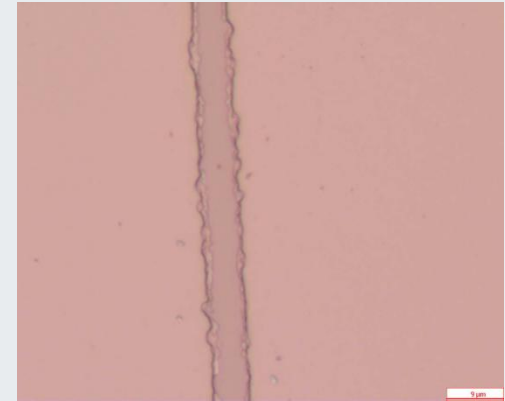
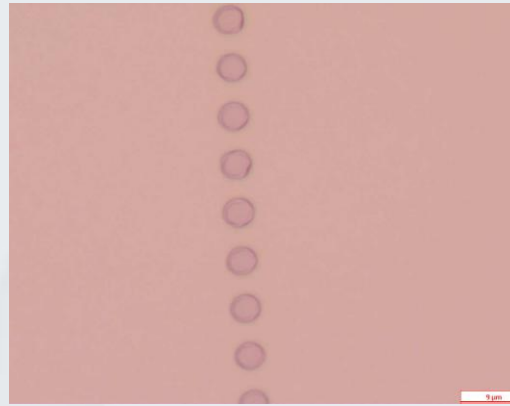
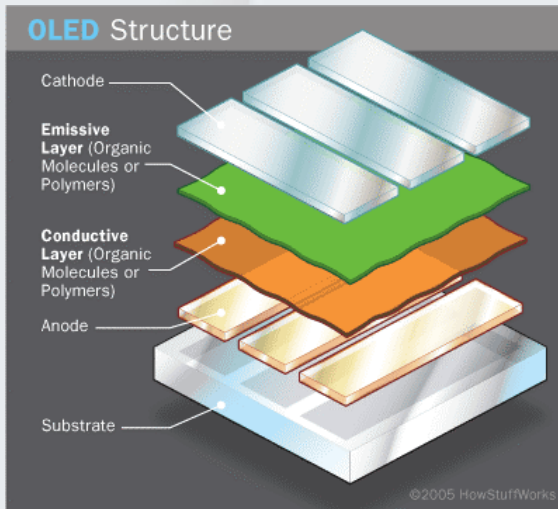
- No backlight - so more efficient and thinner displays
- High contrast ratios, deeper blacks etc
- Richer deeper colours (direct colour production)
- OLED screens are emissive - so no viewing angle problems
- Flexible Screens (newspapers)

The Sony 11-inch OLED TV



Courtesy of Holst

# Patterning Thin Films on Flexible Substrates



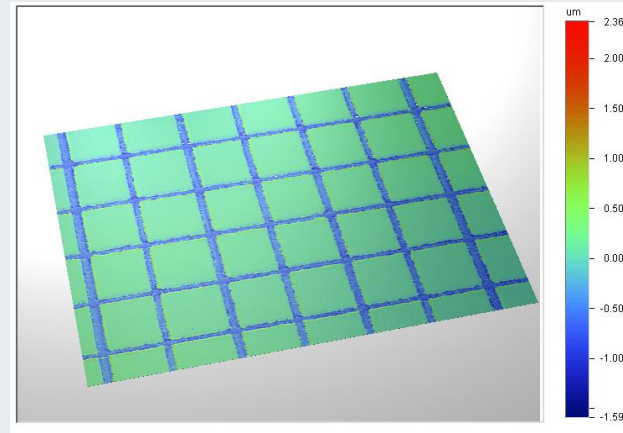
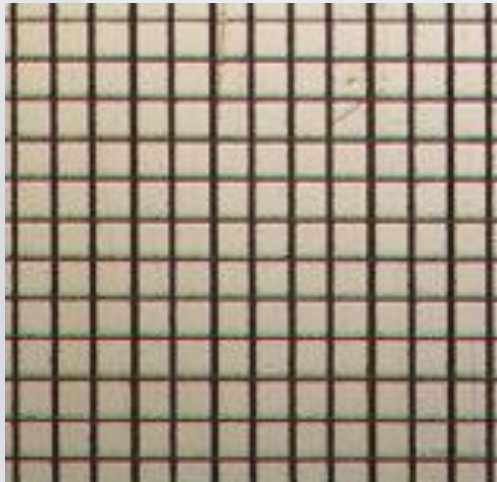
**Laser scribed ITO on Flexible Substrate using 532nm (a) 4 micron spots with depth of 100nm and (b) scanning five times slower. Bar denotes 9 microns**

**Demonstration of thin film removal**

Expert Process Technology

*...20 years experience in laser micromachining*

# Parallel processing with ps laser system



## **OLED Cathode Scribing**

532nm, 30mm/s,

Effective speed of 450mm/s !

15 diffracted spots

Line pitch approx. 85microns

Scribed depth  $d=300\text{nm}$



## 1- SMARTONICS

<http://www.smartonics.eu/>

### Targets:

- Development of **smart Nanomaterials for Organic Electronics** (polymer & small molecule films, plasmonic nanoparticles and super-barriers)
- Development of **smart Technologies** (r2r printing and Organic Vapour Phase Deposition machines combined with precision sensing & **laser tools** and processes).

### Oxford Lasers' task:



- Use their ultrafast laser systems to laser pattern those new materials and make 50  $\mu\text{m}$  tracks with a 50 to 100 nm depth. (area of 30 x 30 cm)

## 2- DIGIPRINT

### Target:

- Large Area High Resolution Digital Printing for Organic Thin Film Transistor Fabrication
- Both “laser-assisted” inkjet printing (IJ) and “laser-induced forward transfer (LIFT)” of functional materials will be investigated.

### Oxford Lasers’ tasks:

- ➔ -Modify material surfaces with ultrafast lasers to make it hydrophobic (allow to control ink droplet size)
- ➔ - LIFT (laser printing method) : 4 um droplet size
- ➔ - High precision laser trimming of transistor (no leakage current, same performance)

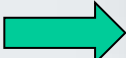

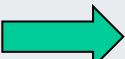
## 3- LASERMICROFAB

<http://lasermicrofab.ntua.gr/>

### Target:

- The development of **advanced laser processing technologies** (micro nano-patterning, printing, curing) for organic electronics and sensors fabrication.

#### Oxford Lasers' tasks:

-  - Selective Laser Micro and Nano-Patterning of thin (500 nm) and of ultrathin (< 50 nm) organic and inorganic layers and multilayer stacks for organic electronics applications.
-  - LIFT (laser printing method)
-  - Beam shaping (round or square spot)



## ***Advanced Laser Micro-machining Solutions***

*Range of Standard System Platforms*

*Laser Micromachining Subcontract Services*

*Laser Micro-machining Expertise*